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PAGE 4143 " RCVD AT 611412004 3:02:32 PM [Eastern Daylight Time] " SVR:USPTO-EFXRE-111 " DNIS:8729306 " CSID: " DURATION (mm-ss);22-16

U.S. Department of Commerce, Patent and Trademark Office					Atty Docket No.		Serial No.		
						2003-0105-02		1	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT						Applicant(s)			
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RBY	A	4,223,279	9/16/80	Bradford, Jr., et al.	331	94.5			
RBS	В	4,455,658	6/19/84	Sutter, et al.	372	38			
NBY	C	4,618,759	10/21/86	Muller, et al.	219	121			
RBY.	D	4,959,840	9/25/90	Robert Akins, et al.	372	57			
RBY	E	5,023,884	6/11/91	Robert Akins, et al.	372	57			
RBZ	P	5,025,445	6/18/91	Anderson, et al.	372	20		-	
RBY	G	5,025,446	6/18/91	Dirk J. Kuizenga	372	21			
RBY	H	5,189,678	2/23/93	Ball, et al.	372	28			
RB F	I	5,313,481	5/17/94	Cook, et al.	372	37			
RBZ	J	5,315,611	5/24/94	Ball, et al.	372	56			
RBZ	K	5,359,620	10/25/94	Robert Akins	372	58		 ':	
RBY	L	5,448,580	9/5/95	Birx, et al.	372	38			
RB's	M	5,471,965	12/5/95	Davorin D. Kapich	123	565			
RBF	N	5,852,621	12/22/98	Richard L. Sandstrom	372	25			
RBF	0	5,863,017	1/26/99	Larson, et al.	248	176.1			
KB.Z	P	5,953,360	9/14/99	Vitruk, et al.	372	87			
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RBZ	R	5,991,324	11/23/99	Knowles, et al.	372	57			
REF	S	6,005,879	12/21/99	Sandstrom, et al.	372	25			
RBY	T	6,016,325	1/18/00	Ness, et al.	372	38			
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		Document	Date	Country	Class	Subclass	Yes	No	
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(Use several sheets if necessary)						Palash Das, et al.				
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RBY	ซ	6,018,537	1/25/00	Hofmann, et al.	372	25				
BBA	V	6,028,880	2/22/00	Carlesi, et al.	372	58	1			
RBZ	W	6,067,306	5/23/00	Sandstrom, et al.	372	38				
RBY	x	6,067,311	5/23/00	Morton, et al.	372	57				
RBS	Y	6,094,448	7/25/00	Fomenkov, et al.	372	102				
RBY	Z	6,104,735	8/15/00	R. Kyle Webb	372	37	 			
PB-2	AA	6,128,323	10/3/00	Myers, et al.	372	38	1			
RBY	AB	6,143,661	11/7/00	Kousai, et al.	438	689	 			
Rp	AÇ	6,151,349	11/21/00	Gong, et al.	372	58				
RBY	AD	6,164,116	12/26/00	Rice, et al.	73	1.72				
RBY	AE	6,192,064	2/20/01	Algots, et al.	372	99				
RBY	AF	6,208,674	3/27/01	Webb, et al.	372	57				
RBJ	AG	6,208,675	3/27/01	R. Kyle Webb	372	58		-		
D37	AH	6,212,211	4/3/01	Azzola, et al.	372	33				
Ross	AI	6,219,368	4/17/01	Sergei Govorkov	372	59	\			
ROS	AJ	6,240,117	5/29/01	Gong, et al.	372	58		-		
RBY	AK	6,317,447	11/13/01	Partio, et al.	372	57				
ROS	AL	6,330,261	12/11/01	Ishihara, et al.	372	38.1		**********		
RBJ	AM	6,414,979	7/2/02	Ujazdowski, et al.	372	87				
RBI	AN	6,477,193	11/5/02	Oliver, et al.	372	58		-		
RBJ	AO	6,549,551	4/15/03	Ness, et al.	372	38				
RBY	AP	6,567,450	5/20/03	Myers, et al.	372	55				
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	-	OTHER	ART (Including	Author, Title, Date, Pe	rtinent Pages, l	Etc.)				
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RB &	AR	6,625,191	9/23/03	Knowles, et al.	372	55			
RBS	AS	09/451,995	11/30/99	Hofmann, et al.					
RBY	AT	10/606,412	6/25/03	Saethre, et al.					
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RBS	AV	10/712,545	11/13/03	R. Kyle Webb, et al.					
RBY	AW	2002/0021728	2/21/02	Newman, et al.	372	55			
RBY	AX	2002/0167986	11/14/02	Pan, et al.	372	55			
RBY	AW	2003/0099269	5/29/03	Ershov, et al.	372	55			
RBY	AY	2004/0022293	2/5/04	Rule, et al.	372	58			
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